Particle Characterization: Module 12, Lecture 35

1. Sketch the design of a VLF cleanroom (CR).

2. Why should stagnant & turbulent flow be avoided in a CR?

3. Write conservation laws for an isothermal CR facility.

4. What are typical initial & boundary conditions for a CR?

5. Sketch quasi steady-state model of a CR.

6. Formulate constrained optimization problem for CR cleanliness.

7. State expression for deposition rate on a wafer in a CR.

8. Identify 3 key parameters that affect particle deposition on a wafer in a CR.

9. How is PWP measured? What is it related to?

10. Sketch typical Pareto diagram of particle sources in a CR. How is this used?